	Application No.	Applicant(s)	
Notice of Allowability	10/725,403	NAKAYAMA ET AL.	
	Examiner	Art Unit	
	Rakesh K. Dhingra	1763	
The MAILING DATE of this communication apperall claims being allowable, PROSECUTION ON THE MERITS IS nerewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI	(OR REMAINS) CLOSED in this app or other appropriate communication GHTS. This application is subject to	olication. If not included will be mailed in due course. THIS	S itive
 This communication is responsive to <u>Applicant's amendme</u> 	<u>nt dt. 6/21/06</u> .		
2. \square The allowed claim(s) is/are <u>2-7,9-15 and 17</u> .	•		±
 3. Acknowledgment is made of a claim for foreign priority un a) All b) Some* c) None of the: 1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 	been received. been received in Application No		
3. Copies of the certified copies of the priority doc	cuments have been received in this i	national stage application from the	
International Bureau (PCT Rule 17.2(a)).	•		
* Certified copies not received:		the theory of the second	
Applicant has THREE MONTHS FROM THE "MAILING DATE" noted below. Failure to timely comply will result in ABANDONM THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file a reply IENT of this application.	complying with the requirements	
 A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give 	itted. Note the attached EXAMINER es reason(s) why the oath or declara	S AMENDMENT or NOTICE OF tion is deficient.	
5. CORRECTED DRAWINGS (as "replacement sheets") mus	st be submitted.		
(a) including changes required by the Notice of Draftspers	son's Patent Drawing Review(PTO-	948) attached	
1) 🗌 hereto or 2) 🗍 to Paper No./Mail Date			
(b) ☐ including changes required by the attached Examiner's Paper No./Mail Date		•	,
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t	.84(c)) should be written on the drawii he header according to 37 CFR 1.121(d).	
 DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT 	sit of BIOLOGICAL MATERIAL r FOR THE DEPOSIT OF BIOLOGIC	must be submitted. Note the AL MATERIAL.	
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Attachment(s) 1. ☐ Notice of References Cited (PTO-892)	5 \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \ \	Patent Application (PTO-152)	
 Notice of References Cited (F10-092) Dotice of Draftperson's Patent Drawing Review (PTO-948) 	6. ☐ Interview Summary		
	Paper No./Mail Da 08), 7. 🛛 Examiner's Amend	te ment/Comment	
 Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 	•		
4. Examiner's Comment Regarding Requirement for Deposit of Biological Material	8. 🛛 Examiner's Stateme	ent of Reasons for Allowance	
or biological material	9. Other		
		Rakesh K. Dhingra	
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EXAMINER'S AMENDMENT

An examiner's amendment to the record appears below. Should the changes and/or additions be unacceptable to applicant, an amendment may be filed as provided by 37 CFR 1.312. To ensure consideration of such an amendment, it MUST be submitted no later than the payment of the issue fee.

Authorization for this examiner's amendment was given in a telephone interview with Damond E. Vadnais on 8/23/06.

The application has been amended as follows:

In the Claims:

Claim 9 (Currently Amended): A plasma processing apparatus comprising:

a vacuum chamber that accommodates an object to be processed, and provides a

plasma process to the object in a vacuum or reduced pressure environment;

a dielectric for transmitting microwaves to said vacuum chamber and for maintaining the

vacuum or reduced environment of said vacuum chamber;

a plate that has slots for guiding the microwaves to said dielectric; and a temperature control mechanism that has a cooling channel between said plate and said dielectric, and controls temperature of said dielectric,

wherein the cooling channel comprises a heat conductive medium therein, and wherein the heat conductive medium is arranged on the surface of said dielectric, on a peripheral portion of said dielectric in a ring shape so as not to close the slots in the plate.

Claim 17 (Currently Amended): A plasma processing apparatus comprising:

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a vacuum chamber that accommodates an object to be processed, and provides a plasma process to the object in a vacuum or reduced pressure environment; a dielectric for transmitting microwaves to said vacuum chamber and for maintaining the vacuum or reduced environment of said vacuum chamber; a plate that has slots for guiding the microwaves to said dielectric; and a temperature control mechanism that has a cooling channel between said plate and said dielectric, and controls temperature of said dielectric, wherein the cooling channel is supplied with coolant; a waveguide for guiding the microwaves to said plate, wherein plural holes are formed in a part of said waveguide, such that the coolant is allowed to pass through the holes.

a waveguide for guiding the microwaves to said plate, wherein plural notes are formed in a part of said waveguide, such that the coolant is allowed to pass through the holes and such that the microwaves are prevented from transmitting through the holes; and a partition, formed on said waveguide between the part of said waveguide having the holes and a microwave source for supplying the microwaves, for preventing the coolant from moving along said waveguide to the microwave source, wherein the partition is made of a high dielectric <u>loss</u> material.

Allowable Subject Matter

Claims 9, 2-7, 10-15 and 17 allowed.

REASONS FOR ALLOWANCE

The following is an examiner's statement of reasons for allowance:

Regarding Claim 9: Closest prior art (Yamazaki et al – US Patent No. 6,059,922) does not teach claim limitation interalia, "a plate that has slots for guiding the microwaves to said dielectric; and

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a temperature control mechanism that has a cooling channel between said plate and said dielectric, and controls temperature of said dielectric,

wherein the cooling channel comprises a heat conductive medium therein, and wherein the heat conductive medium is arranged on the surface of said dielectric, on a peripheral portion of said dielectric in a ring shape so as not to close the slots in the plate."

Regarding Claim 17: Closest prior art (JP 2-302507) does not teach claim limitation interalia, a partition, formed on said waveguide between the part of said waveguide having the holes and a microwave source for supplying the microwaves, for preventing the coolant from moving along said waveguide to the microwave source, wherein the partition is made of a high dielectric <u>loss</u> material.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Rakesh K. Dhingra whose telephone number is (571)-272-5959. The examiner can normally be reached on 8:30 -6:00 (Monday - Friday).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Parviz Hassanzadeh can be reached on (571)-272-1435. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Rakesh Dhingra

Parviz Hassanzadeh Supervisory Patent Examiner Art Unit 1763